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APPLICATION NO.	FILIN	G DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/642,656	0/642,656 08/19/2003		Seo-Hyun Cho	1349.1276	3051	
21171	7590	02/01/2006		EXAM	EXAMINER	
STAAS & I	HALSEY LI	LP	MCPHERSON, JOHN A			
SUITE 700 1201 NEW Y	ORK AVEN	IUE, N.W.		ART UNIT	PAPER NUMBER	
	ON, DC 20	•	1756			
				DATE MAILED: 02/01/2000	5	

Please find below and/or attached an Office communication concerning this application or proceeding.

<u> </u>					,
		App	olication No.	Applicant(s)	
			642,656	CHO ET AL.	
	Office Action Summary	Exa	miner	Art Unit	
			n A. McPherson	1756	
The Period for Re	e MAILING DATE of this commun	ication appears	on the cover sheet w	with the correspondence ac	ddress
A SHORT WHICHEY - Extensions after SIX (6 - If NO perio - Failure to r - Any reply r	ENED STATUTORY PERIOD F VER IS LONGER, FROM THE N of time may be available under the provisions b) MONTHS from the mailing date of this common of for reply is specified above, the maximum steply within the set or extended period for reply eccived by the Office later than three months ent term adjustment. See 37 CFR 1.704(b).	MAILING DATE ( s of 37 CFR 1.136(a). I nunication. ratutory period will apply will, by statute, cause	OF THIS COMMUN in no event, however, may a y and will expire SIX (6) MO the application to become it	IICATION. a reply be timely filed  ONTHS from the mailing date of this of ABANDONED (35 U.S.C. § 133).	
Status					•
1)⊠ Res 2a)□ This 3)□ Sind	sponsive to communication(s) files action is <b>FINAL</b> .  The this application is in condition accordance with the pract	2b)⊠ This action for allowance e	on is non-final. xcept for formal ma	•	e merits is
Disposition o	of Claims				
4a) 0 5)	m(s) 1-5,7-10 and 12-30 is/are portion of the above claim(s) 1-3 is/are m(s) is/are allowed.  m(s) 4,5,7-10 and 12-30 is/are m(s) is/are objected to.  m(s) are subject to restrict appers  specification is objected to by the drawing(s) filed on is/are discant may not request that any objection is objected to by the drawing of the drawing objected to by the drawing objected to be	withdrawn from ejected. ction and/or elected e Examiner. a) accepted	consideration.  etion requirement.  or b) objected to	•	
	lacement drawing sheet(s) including oath or declaration is objected to				• •
Priority unde	r 35 U.S.C. § 119				
12)□ Ackr a)□ Al 1.□ 2.□ 3.□	nowledgment is made of a claim	documents hav documents hav of the priority do nal Bureau (PC	e been received. e been received in a ccuments have bee T Rule 17.2(a)).	Application No n received in this National	Stage
2)  Notice of E 3)  Information	References Cited (PTO-892) Praftsperson's Patent Drawing Review (F n Disclosure Statement(s) (PTO-1449 or s)/Mail Date		Paper No	Summary (PTO-413) (s)/Mail Date Informal Patent Application (PTG	O-152)

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#### **DETAILED ACTION**

### Continued Examination Under 37 CFR 1.114

- 1. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 11/17/05 has been entered.
- 2. The Amendment filed 11/17/05 successfully overcomes the rejections set forth in paragraphs 3 and 4 of the Office Action mailed 8/19/05. Accordingly, these rejections are withdrawn.

## Claim Rejections - 35 USC § 102

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 4, 5, 7-10 and 12-30 are rejected under 35 U.S.C. 102(b) as being anticipated by US 6,162,589 to Chen et al. (Chen). Chen discloses a method of manufacturing a thermal inkjet printhead comprising the steps of forming a layer of slow-crosslinking polymer, for example an epoxy or a polyimide, on a substrate;

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exposing the polymer layer through a single mask having multi-density levels to allow different dosages of electromagnetic energy to expose the polymer; developing to remove non cross-linked material to form a fluid-well chamber and an orifice chamber; and etching the through backside of the substrate to create a fluid feed channel. See column 8, lines 5-21 and Figures 9E-G.

Furthermore, as shown in Figure 9E, the multi-density level mask transmits electromagnetic radiation having regions of strong intensity 11 (corresponding to the first part having a relatively high UV transmission rate of the present invention), regions with a low dose of electromagnetic energy 12 (corresponding to the second and forth parts having the same relatively low UV transmission rate of the present invention), and provides a region where electromagnetic radiation is not transmitted at the orifice opening 42 (corresponding to the third part having a UV transmission rate of 0% of the present invention), wherein the region where electromagnetic radiation is not transmitted (i.e. the third part) is between the regions with a low dose of electromagnetic energy (i.e. the second and forth parts).

#### Response to Arguments

4. Applicant's arguments filed 11/17/05 have been fully considered but they are not persuasive. Applicant argues that the mask of Chen [as shown in figure 6A] has an opaque area 142 within a partially opaque area 144. Thus, the opaque area 142 is not between different parts having a same UV transmission rate. However, Figure 6A of Chen is a top view of multi-density level mask 140. If the mask of Chen was viewed as

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a cross section, similar to the view of photomask 108' in Figure 4C of the present invention, then the mask of Chen would comprise an opaque area between two partially opaque areas. This is clearly show in Figure 9E of Chen, where the length of the arrows, or lack thereof, represents the transmission rate of the mask. Note that the orifice opening 42, patterned by the opaque area 142 of multi-density level mask 140, is between two regions with a low dosage of electromagnetic energy 12, each patterned by partially opaque area 144 of multi-density level mask 140.

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5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to John A. McPherson whose telephone number is (571) 272-1386. The examiner can normally be reached on Monday through Friday, 8:00 AM to 4:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark Huff can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

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you have questions on access to the Private PAIR system, contact the Electronic

Business Center (EBC) at 866-217-9197 (toll-free).

John A. McPherson Primary Examiner Art Unit 1756

JAM 1/30/06